Total Pages: 2 c. Explain why etch rate of SI in CF4 + H2 plasma decreases Roll No. with increasing percent of Hydrogen concentration. 5 8857 5th Sem. Electronics a. Describe the feature size control and an-isotropic BT-5/D07 MICROELECTRONICS etching. b. Describe the e-beam lithography techniqe for VLSI PAPER - ECE-309E Maximum Marks: 100 circuit's fabrication. Time: 3 Hrs. Note: Attempt any five questions in all, selecting at least one UNIT-III Describe the atomistic theory of Diffusion in solids. 10 question from each unit. All questions carry equal marks. b. Describe the evaluation techniques for the characteriza-UNIT-I a. Explain the process step for the preparation of Electronic tion of diffused layer? a. Describe the Range theory in ion implantation and Grade Silicon (EGS) and highlight the extraction of importance of retrograde diffusion. various by-products. b. Highlight the various advantages of lon implantation as b. What are the problem associated with metallization using compared to conventional diffusion techniques. PVD and how to overcome these problems? 2. a. Explain the Oxide growth kinetics with suitable model 10 UNIT-IV Describe the twin tub CMOS IC fabrication process b. Knowing that one mole of silicon is consumed in one sequence and highlight the various mask requirements. mole of SiO2 growth; calculate the thickness of silicon consumed in the thermal growht of oxide of layer Describe the various Isolation techniques. thickness = X. Given : molecular weight of Si and SiO, Discuss the various package types used in VLSI circuits. as 28.9 gm/mole and 60.08 g/mole respectively. Density of Si and SiO2 is 2.46 gm/cm3 and 2.34 gm/cm3 b. What are Pakage design considerations ? Discuss in respectively. c. Write the advantages of High pressure oxidation. detail. UNIT-II 3. a. Discuss the difference between chemical assisted ion beam etching and ion assited chemical etching. b. Explain the advantages and disadvantages of Lift off technique. (5th sem. Electronics) 40 (5th sem. Electronics)

10

10

12

10